## WHAT IS CLAIMED IS:

1. A laminated board comprising a prepreg sheet or prepreg sheets prepared by impregnating a reinforcing fiber material with the thermosetting low-dielectric resin composition comprising a component (a): siloxane-modified polyimide, component (b): a compound containing 2 methylallyl groups and having the following formula (1) or a compound containing 3 allyl groups or 3 methylallyl groups and having the following formula (1A), and component (c): a compound containing at least 2 maleimide groups.

Formula (1):

$$\begin{array}{c|c} & CH_3 \\ \hline & CH_3 \\ \hline & CH_3 \\ \hline & CH_3 \\ \end{array}$$

Formula (1A):

$$\begin{array}{c|c}
 & R \\
 & N \\
 & N \\
 & N \\
 & R \\
 & R
\end{array}$$
(1A)

wherein R is a hydrogen atom or methyl group.

2. The laminated board according to claim 1, wherein the laminated board is a metal-clad laminate formed of the laminated

board and a metal foil or foils which is or are stacked on and integrated with one surface or both surfaces of the laminated board.

- 3. The laminated board according to claim 2, wherein the metalclad laminate is formed of a sheet or sheets of a prepreg impregnated with the thermosetting low-dielectric resin composition in a semicured state or a cured state and a metal foil or metal foils is/are laminated on and integrated with the prepreg.
- 4. The laminated board according to claim 1, wherein the reinforcing fiber material is a fabric or a non-woven fabric formed of at least one member selected from the group consisting of an aramid fiber, an aromatic polyester fiber and a tetrafluorocarbon fiber.
- 5. The laminated board according to claim 1, wherein the metal foil is a metal foil formed of at least one member selected from the group consisting of copper, cupronickel, silver, iron, 42 alloy and stainless steel.
- 6. A circuit laminate material comprising either a peeling-off layer or a metal foil and the thermosetting low-dielectric resin composition comprising a component (a): siloxane-modified polyimide, component (b): a compound containing 2 methylallyl groups and having the following formula (1) or a compound containing 3 allyl groups or 3 methylallyl groups and having the following formula (1A), and component (c): a compound containing at least 2 maleimide groups. Formula (1):

$$\begin{array}{c|c} & CH_3 \\ \hline & CH_3 \\ \hline & CH_3 \\ \end{array}$$

Formula (1A):

$$\begin{array}{c|c}
 & R \\
 & O \\
 & N \\$$

wherein R is a hydrogen atom or methyl group, which thermosetting low-dielectric resin composition is an adhesive layer laminated on one surface of the peeling-off layer or the metal foil.

7. The circuit laminate material according to claim 6, wherein the siloxane-modified polyimide as a component (a) contains 90 to 40 mol% of at least one of structural units of the following formula (2a) and 10 to 60 mol% of at least one of structural units of the following formula (2b) when the component (b) is the compound of the formula (1).

## Formula (2a):

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Formula (2b):

wherein X is a tetravalent aromatic group and is any one of a 3,3',4,4'-diphenylsulfone structure, a 3,3',4,4'-biphenyl structure and 2,3',3,4'-biphenyl structure, Ar is a divalent group selected from aromatic-ring-possessing groups of the following formula (3), R is  $-CH_2OC_6H_4$ - whose methylen group is bonded to Si or an alkylene group having 1 to 10 carbon atoms, and n is an integer of 1 to 20,

## Formula (3):

wherein each of  $R_1$ ,  $R_2$ ,  $R_3$  and  $R_4$  is independently a hydrogen atom, or an alkyl or alkoxy group having 1 to 4 carbon atoms provided that all of these are hydrogen atoms in no case.

8. The circuit laminate material according to claim 6, wherein the siloxane-modified polyimide as a component (a) contains 90 to 40 mol% of at least one of structural units of the following formula (2a') and 10 to 60 mol% of structural units of the following formula (2b') when the component (b) has the formula (1A).

Formula (2a'):

Formula (2b'):

$$-N \longrightarrow X' \longrightarrow N \longrightarrow R \longrightarrow Si \longrightarrow (0Si)_{7}R \longrightarrow (2b')$$

$$CH_{3} \longrightarrow CH_{3}$$

$$CH_{3} \longrightarrow CH_{3}$$

wherein X is a direct bond or any one of binding groups of -O,  $-SO_2$ , -CO,  $-C(CH_3)_2$ ,  $-C(CF_3)_2$  and  $-COOCH_2CH_2OCO$ . Ar is a divalent group selected from aromatic-ring-possessing groups of the following formula (3A), R is  $-CH_2OC_2H_4$ — whose methylen group is bonded to Si or an alkylene group having 1 to 10 carbon atoms, and n is an integer of 1 to 20,

Formula (3A):

wherein each of  $R_1$ ,  $R_2$ ,  $R_3$  and  $R_4$  is independently a hydrogen atom or an alkyl or alkoxy group having 1 to 4 carbon atoms provided that all of these are hydrogen atoms in no case.

9. The circuit laminate material according to claim 6, wherein the siloxane-modified polyimide as a component (a) contains 90 to 40 mol% of at least one of structural units of the following formula (2a) and 10 to 60 mol% of structural units of the following formula (2b) when the component (b) has the formula (1A).

Formula (2a):

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Formula (2b):

$$\begin{array}{c|c} CII_3 & CII_3 \\ \hline N-R-Si-(OSi)_7R- \\ \hline CII_3 & CII_3 \end{array}$$

wherein X is a tetravalent aromatic group and is any one of a 3,3',4,4'-diphenylsulfone structure, a 3,3',4,4'-biphenyl structure and 2,3',3,4'-biphenyl structure, Ar is a divalent group selected from aromatic-ring-possessing groups of the following formula (3A) recited claim 4, R is  $-CH_2OC_6H_4$ - whose methylen group is bonded to Si or an alkylene group having 1 to 10 carbon atoms, and n is an integer of 1 to 20.

- 10. The circuit laminate material according to claim 6, wherein the metal foil has a thickness of 10 to 300  $\mu m$ .
- 11. The circuit laminate material according to claim 6, wherein the adhesive layer has a peeling-off layer formed on one surface opposite to the metal foil or the film.